

Abstract of the Disclosure

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5 A resist pattern forming apparatus comprising a  
controller having a controlling portion that controls a  
processing of a coating and developing apparatus with a  
coating unit and a developing unit being provided  
therewith and an aligner being connected thereto, while  
an inspecting portion and the like measures at least  
one of a plurality of measurement items selected from,  
a reflection ratio and a film thickness of a base film  
10 and a resist film, a line width after the development,  
an accuracy that the base film matches with a resist  
pattern, a defect after the development, and so on. The  
measured data is transmitted to the controller. At the  
controller, a parameter subject to an amendment is  
15 selected based on the corresponding data of each of the  
measurement item such as the film thickness of the  
resist and the line width after the development, and  
the amendment of the parameters subject to the  
amendment is performed. As a result, the amending  
20 operation is facilitated by a reduced workload of an  
operator and in the same time, the appropriate  
amendment can be performed.

181 words

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